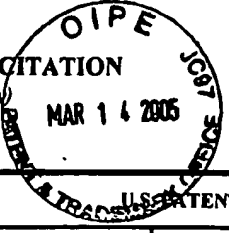


<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>				Docket Number (Optional) <b>34261-8500</b>		Application Number <b>10/680,960</b>		
				Applicant(s) <b>Howard Ge et al.</b>				
				Filing Date <b>10/07/2003</b>		Group Art Unit <b>1756</b>		
<b>U.S. PATENT DOCUMENTS</b>								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
DCD		5,032,217	7/16/1991	Tanaka				
DCD		2,046,596	7/7/1936	Zwiebel				
DCD		5,455,062	10/3/1995	Muhlfriedal et al.				
DCD		5,498,449	3/12/1996	Bae				
DCD		6,403,500	6/11/2002	Yu et al.				
<b>U.S. PATENT APPLICATION PUBLICATIONS</b>								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
DCD		2002/0092917	7/18/2002	Ko et al.				
<b>FOREIGN PATENT DOCUMENTS</b>								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
DCD		11-010041	19-01-1999	Patent Abstracts of Japan			✓	
DCD		0 654 306	27-05-1994	Europe			✓	
<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
DCD		<b>KUTCHOUKOV V G ET AL.:</b> "New photoresist coating method for 3-D structured wafers" <b>SENSORS AND ACTUATORS A, ELSEVIER SEQUOIA S.A., LAUSANNE, CHI, vol. 85, no. 1-3, 25 August 2000 pages 377-383.</b>						
EXAMINER				DATE CONSIDERED				
/Daborah Chacko-Davis/				06/08/2006				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>				Docket Number (Optional)		Application Number	
				34261-8500		10/380,960	
				Applicant(s)			
				Ge et al.			
				Filing Date		Group Art Unit	
				10/07/2003		1756	

U. S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
DCD		5,762,708	06/09/1998	Motada et al.	118	52	
DCD		6,174,561	01/16/2001	Taylor	427	96	

U.S. PATENT APPLICATION PUBLICATIONS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
DCD		617,332	09/28/1994	EP				

OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>		
DCD		Anonymous, "Process to Clean Metal Surfaces Prior to Photoresist Apply" (XP 007116262A) Research Disclosure – Kenneth Mason Publications, Vol. 324, No. 31, Abstract, April 1991
DCD		Written Opinion of the International Searching Authority, the European Patent Office for the PCT counterpart application PCT/US2004/023587

EXAMINER: /Daborah Chacko-Davis/	DATE CONSIDERED 06/08/2006
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